

Fig. 1

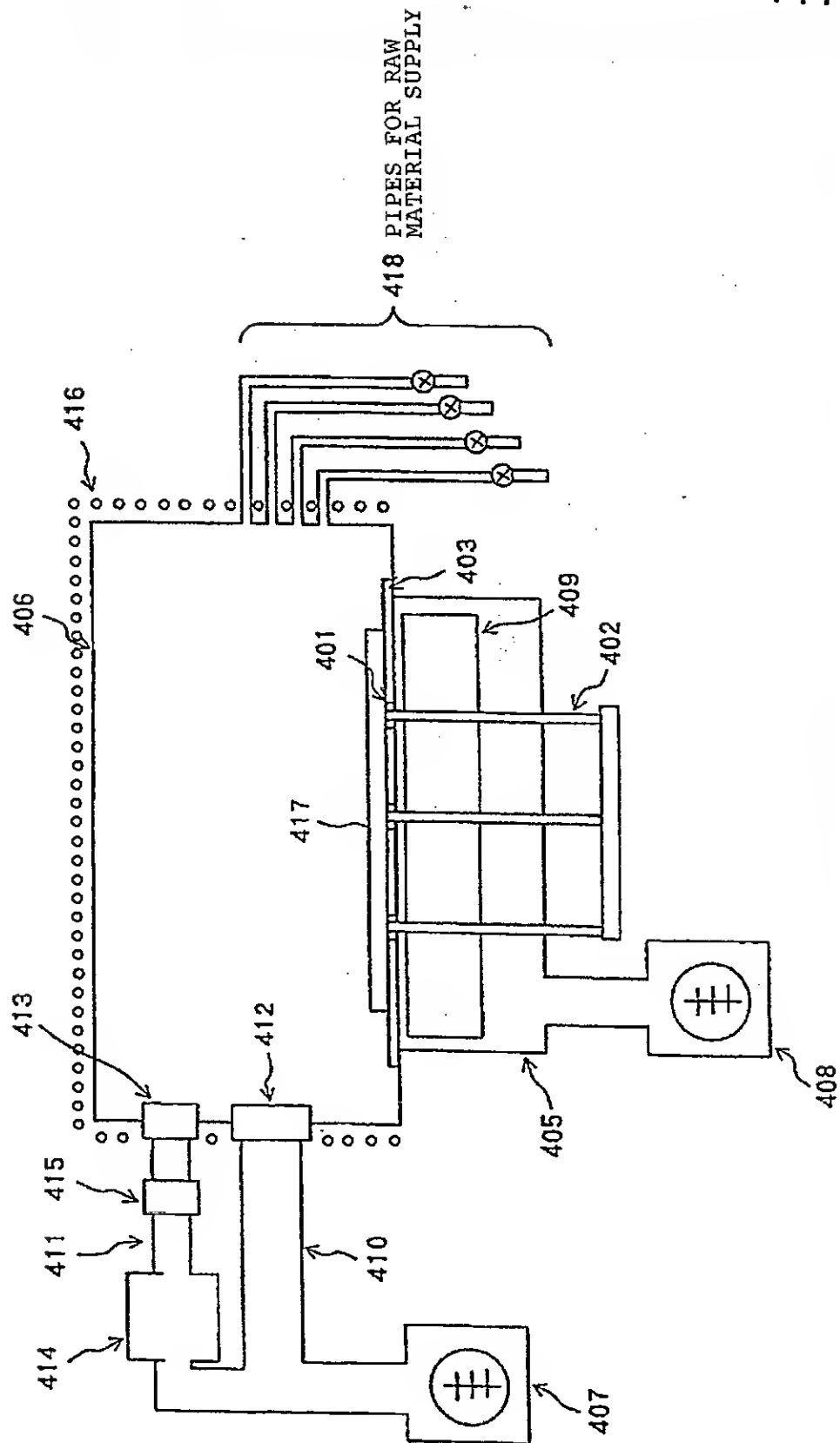
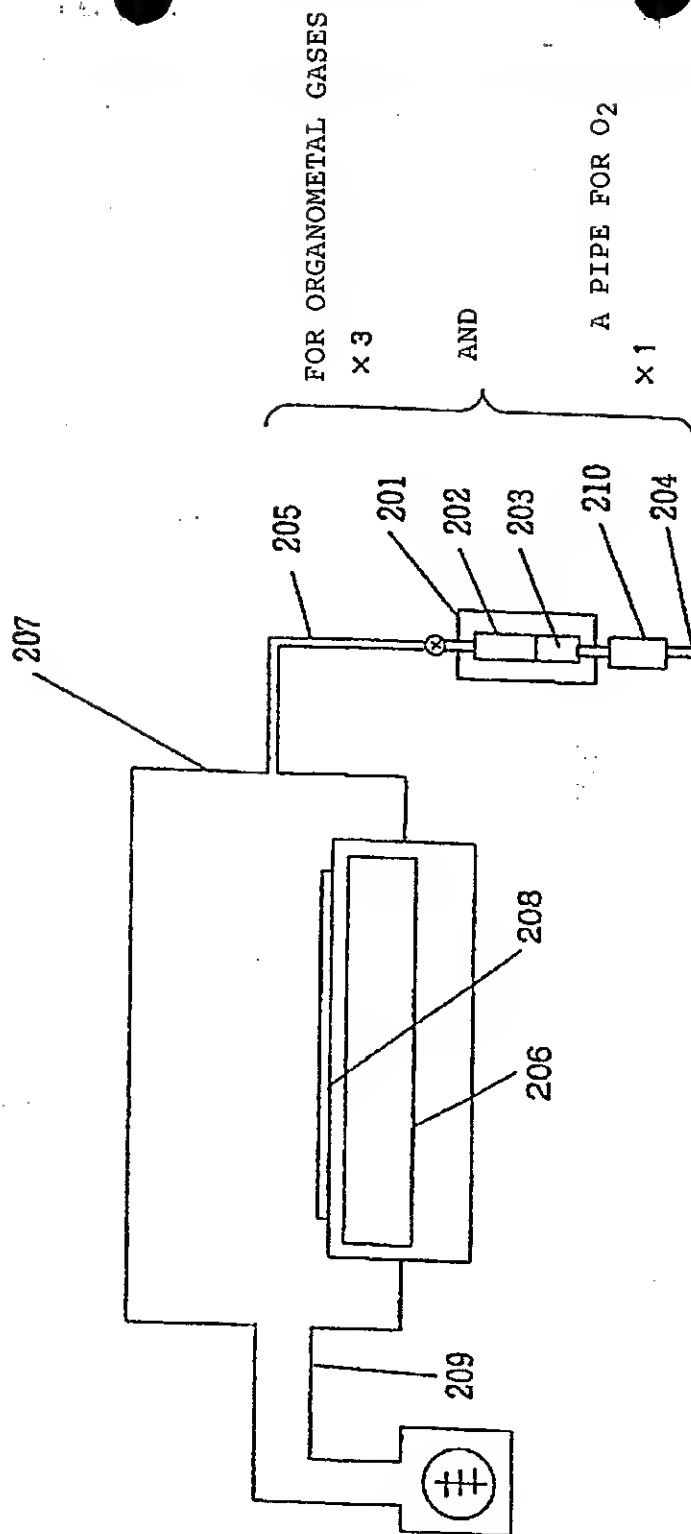


Fig. 2



T00210-10444260

Fig. 3

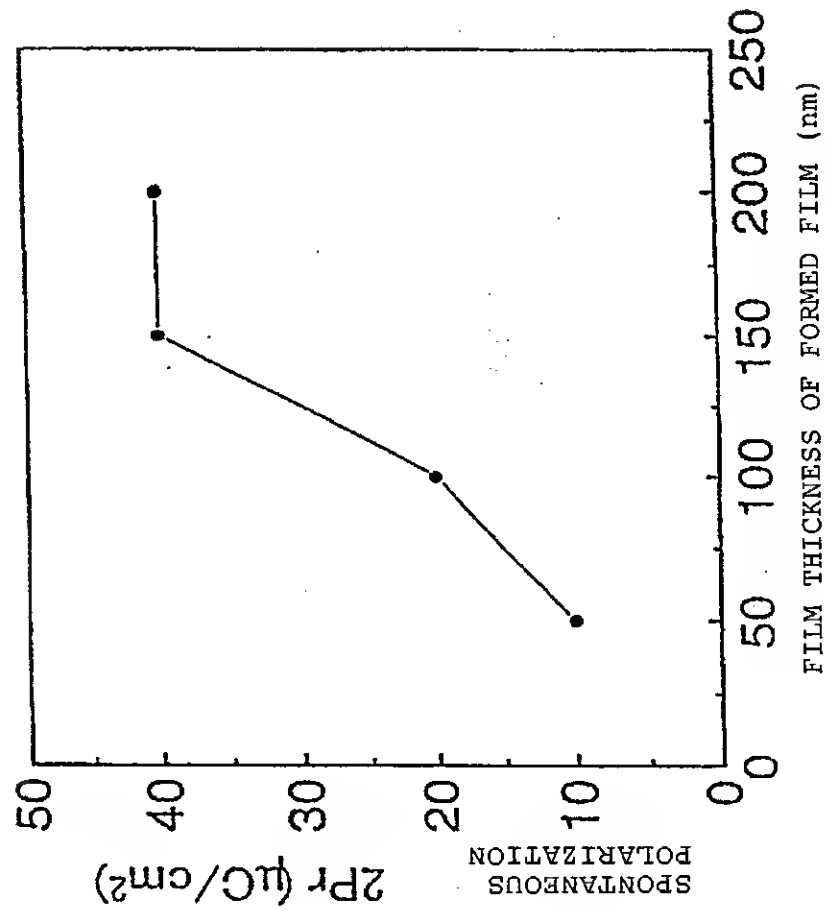


Fig. 4

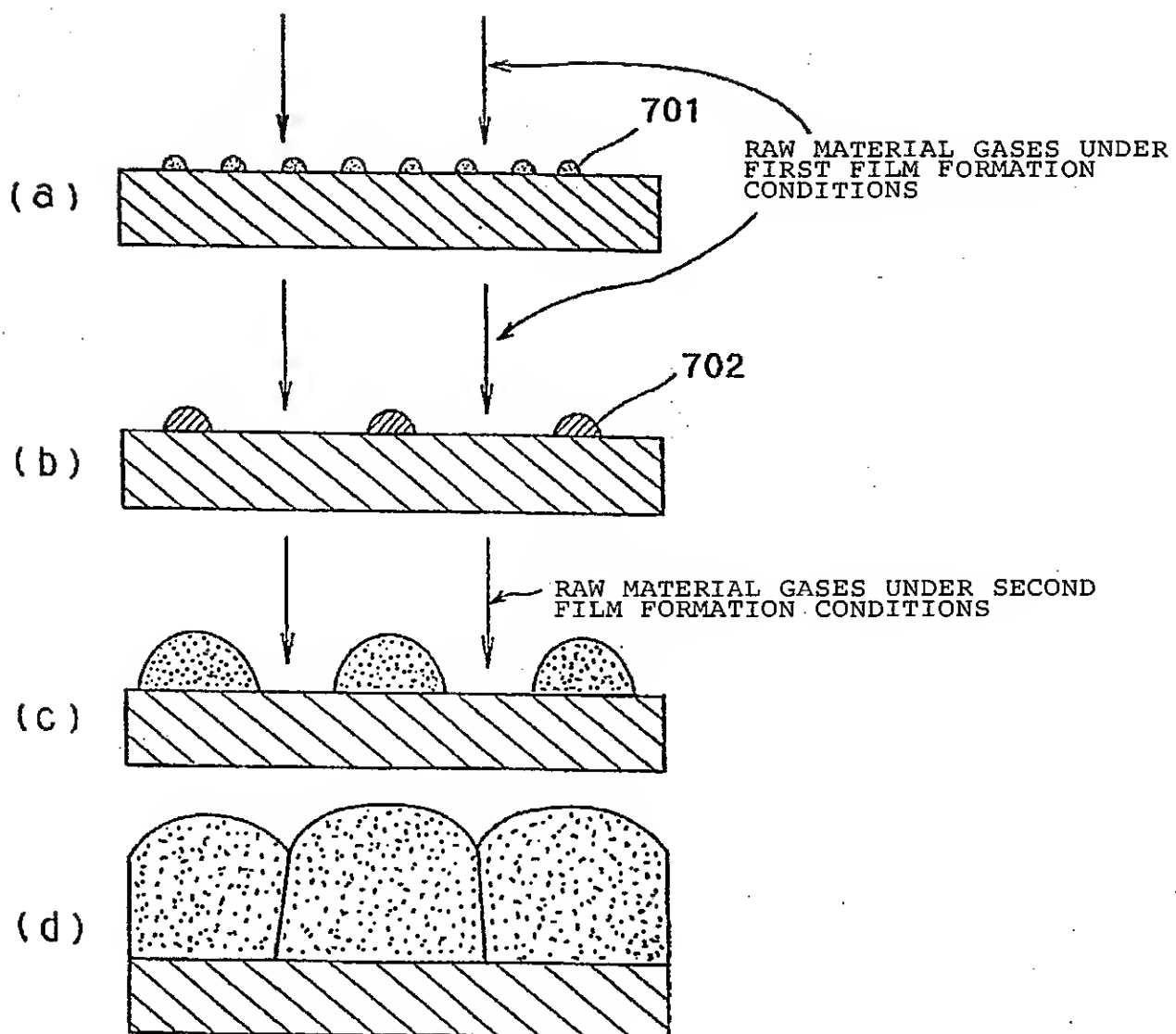


Fig. 5

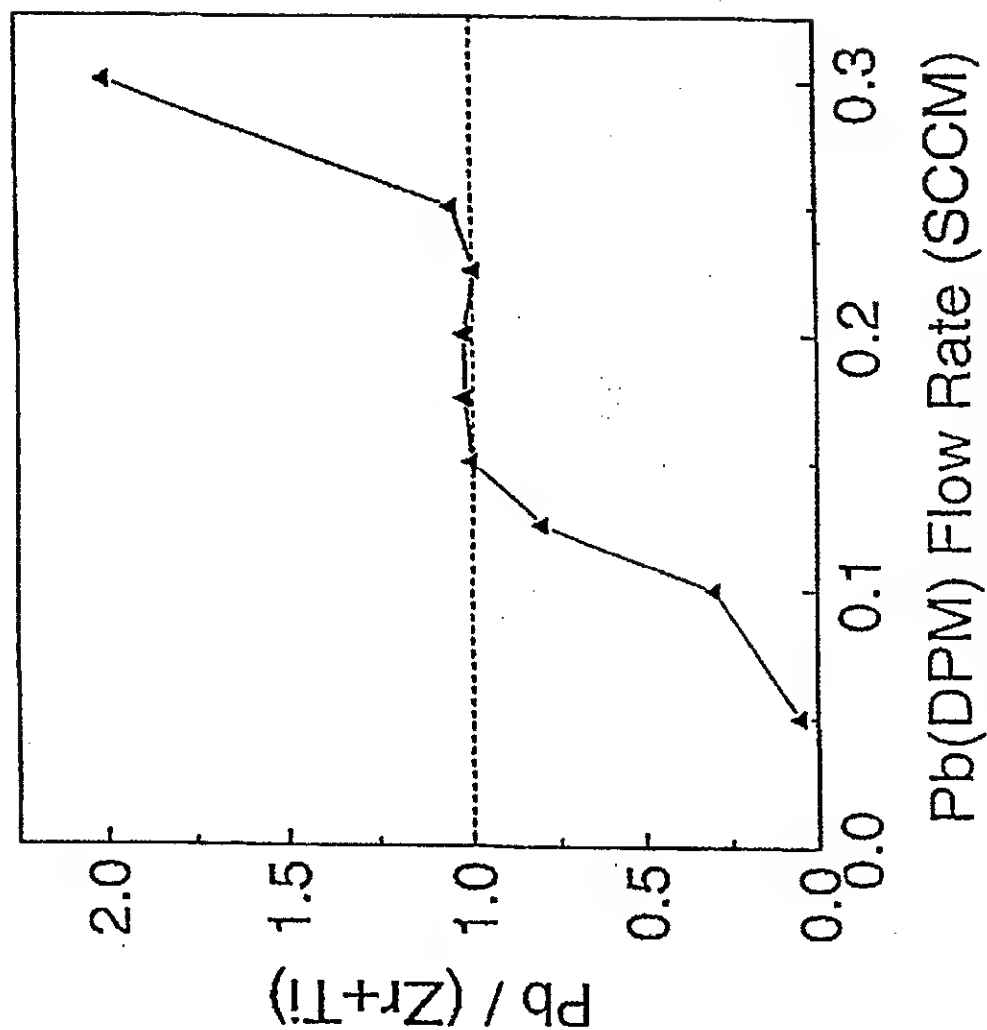


Fig. 6

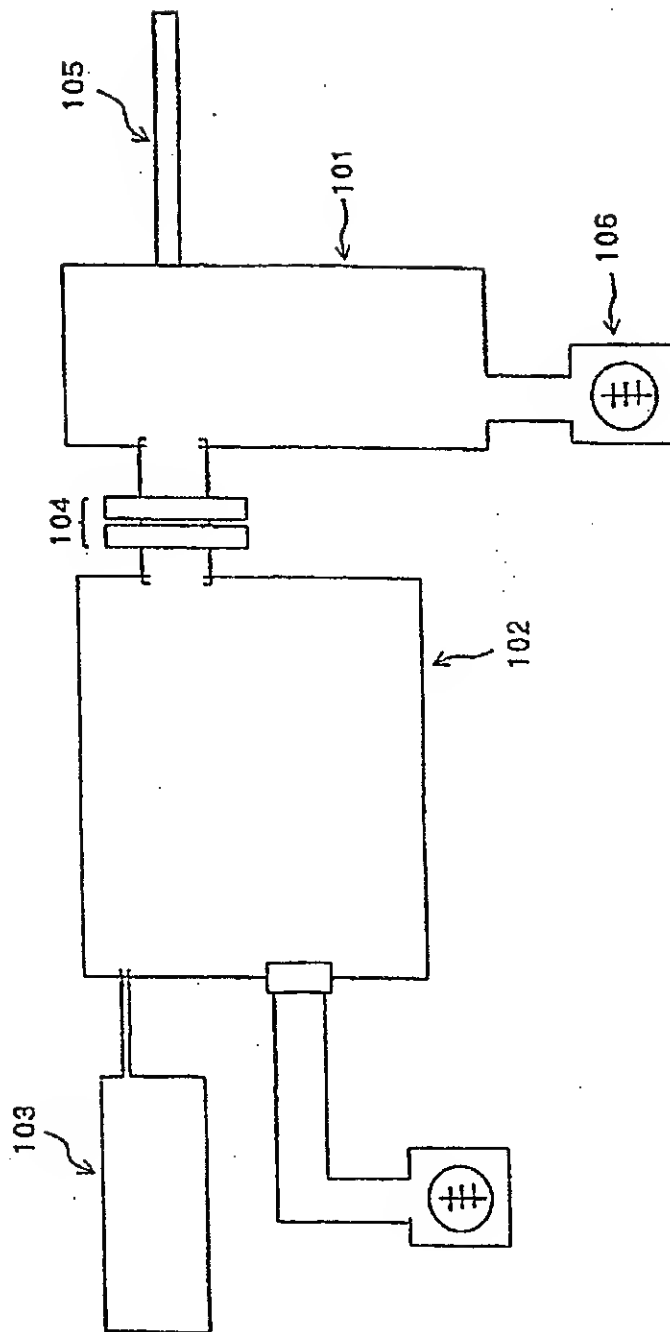


Fig. 7

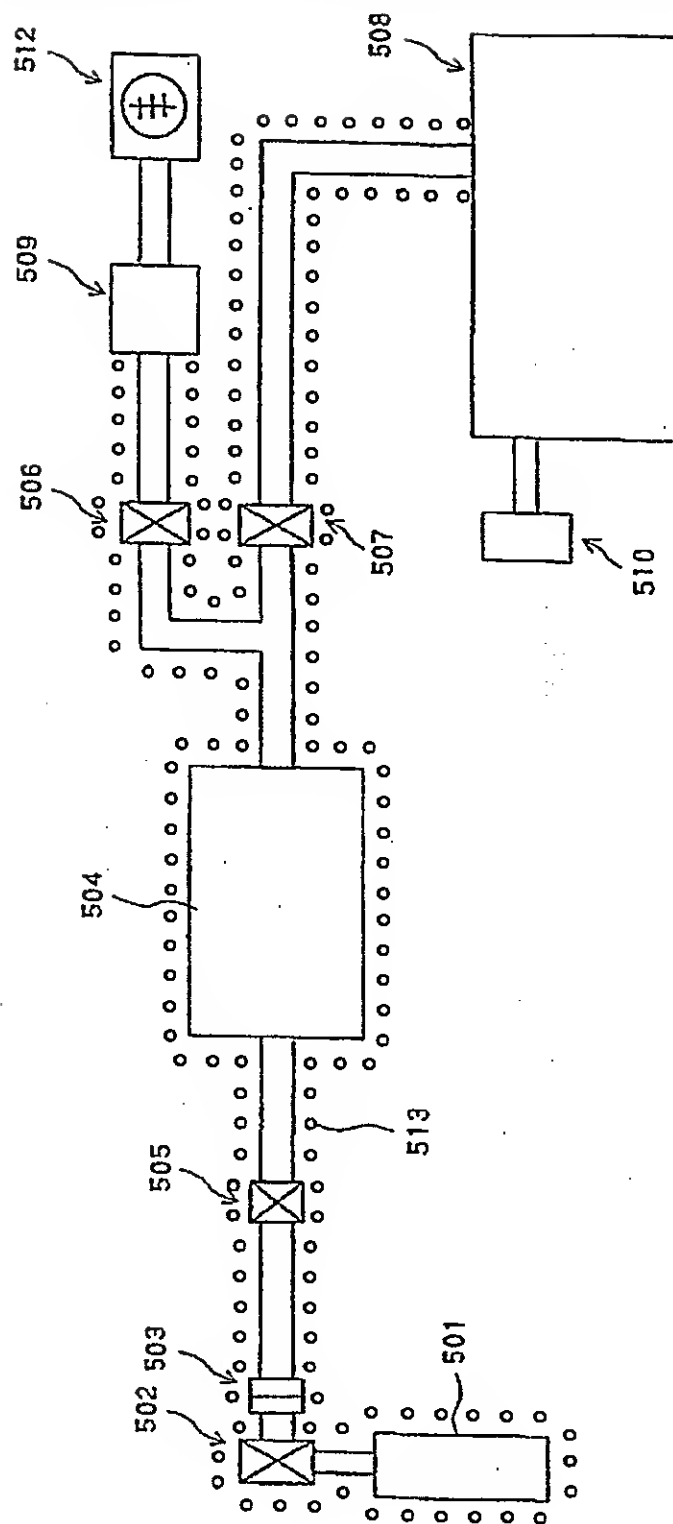
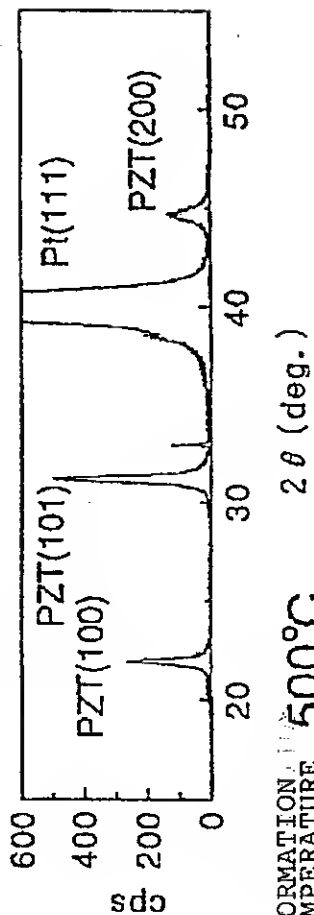


Fig. 8

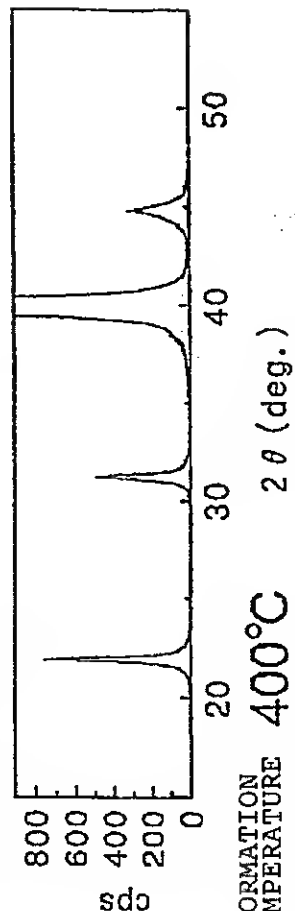
FILM FORMATION TEMPERATURE

600°C



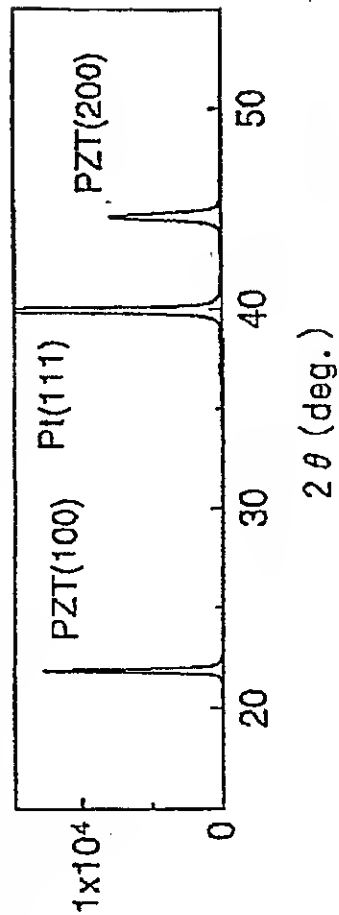
FILM FORMATION TEMPERATURE

500°C



FILM FORMATION TEMPERATURE

400°C





T06270-10244450

Fig. 9

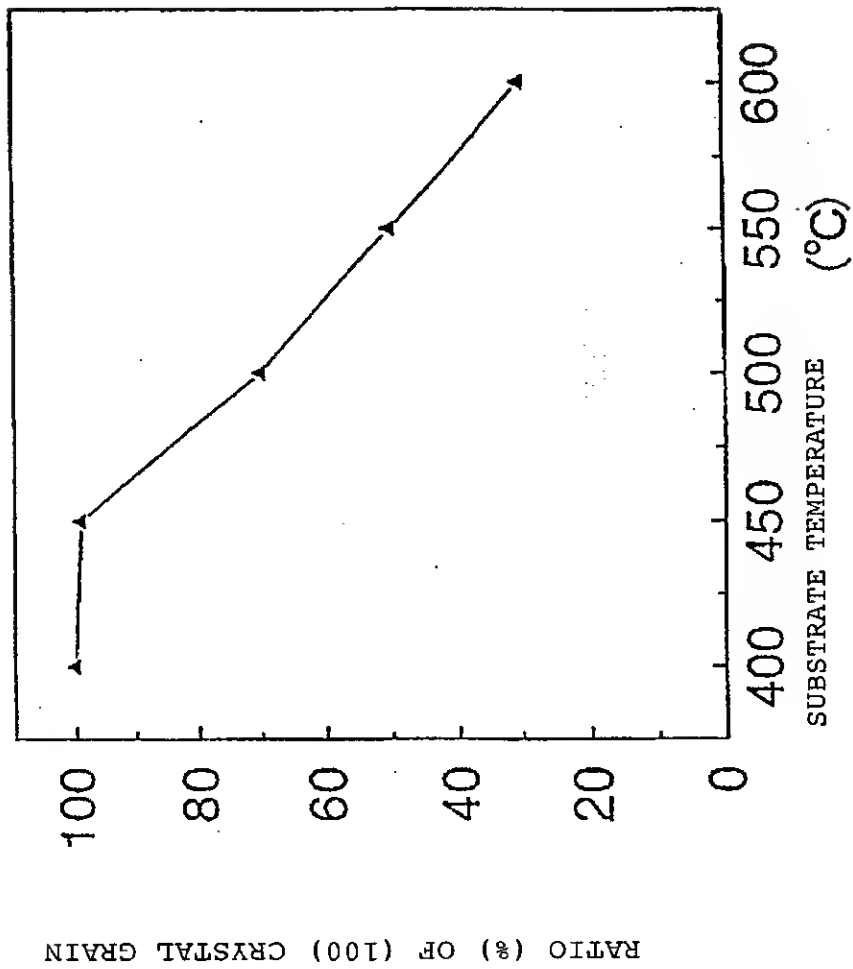


Fig. 10

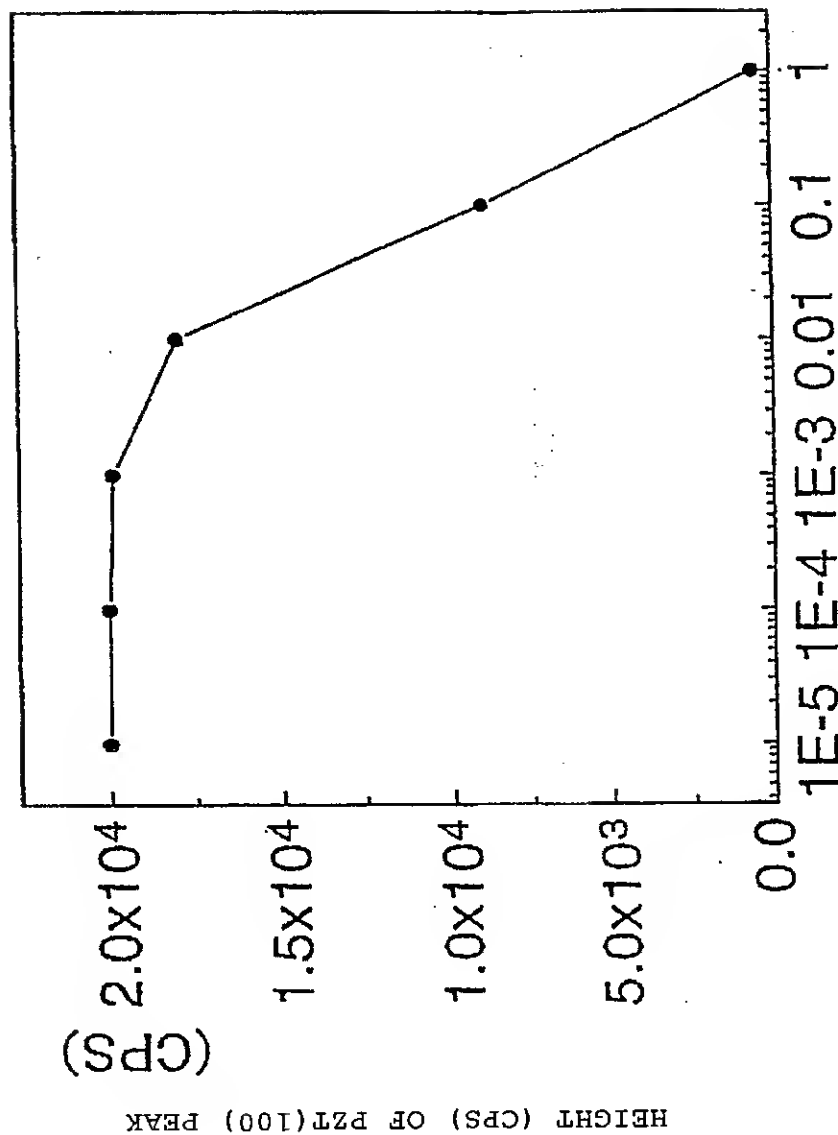
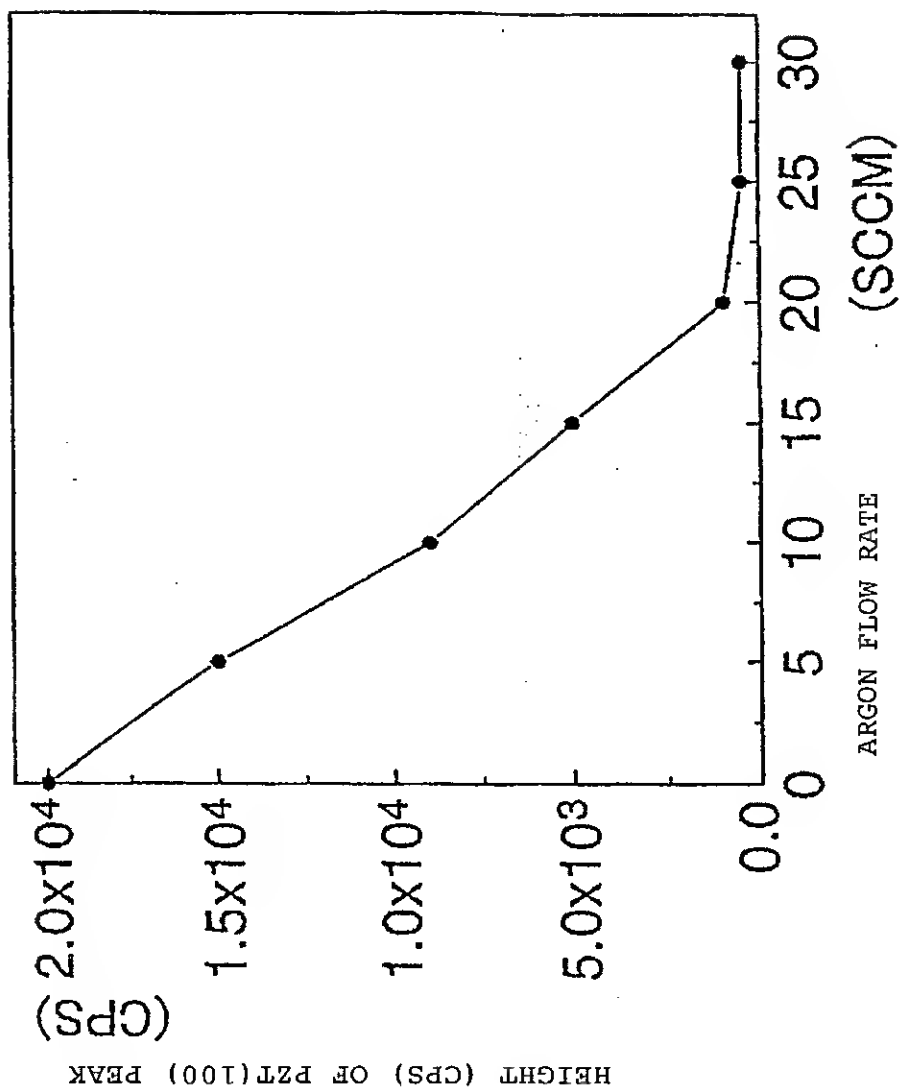


Fig. 11



FORMED POLARIZATION

Fig. 12

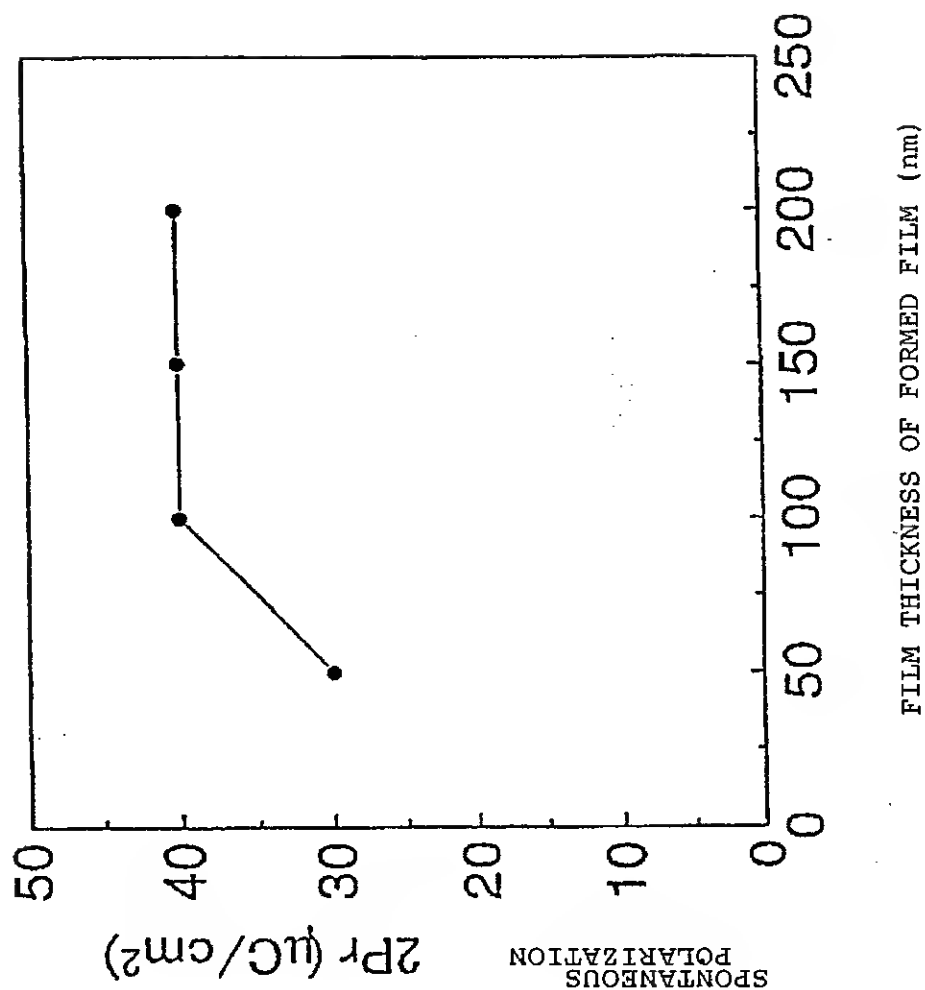


Fig. 13

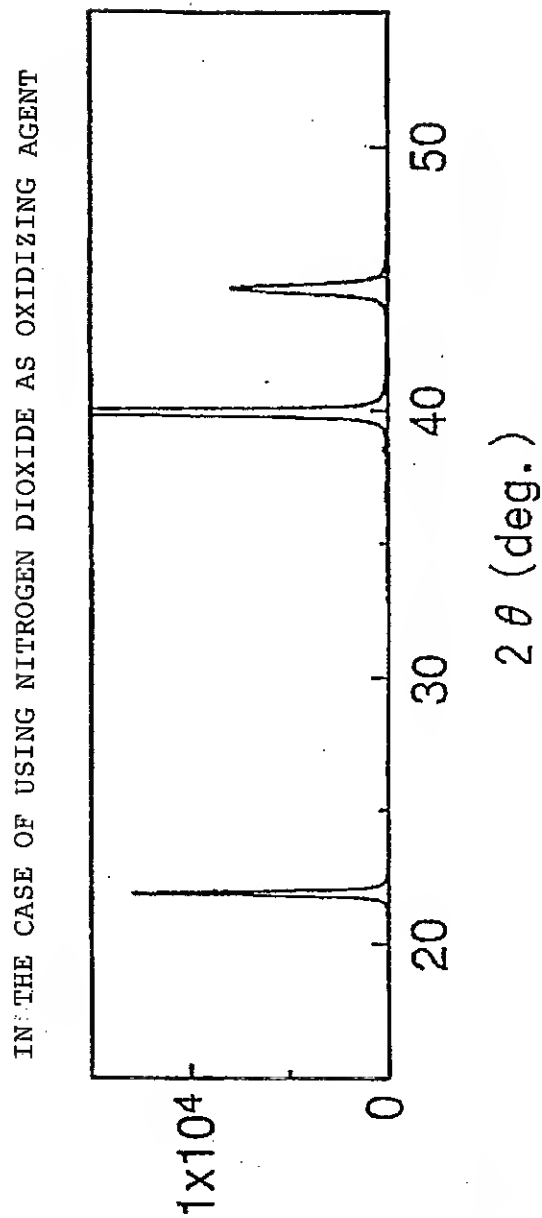
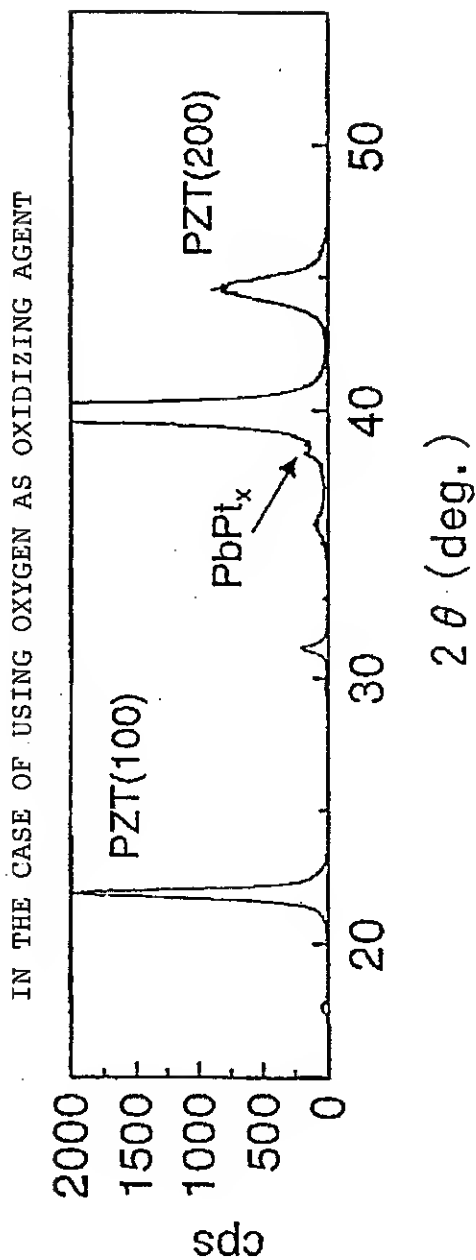


Fig. 14

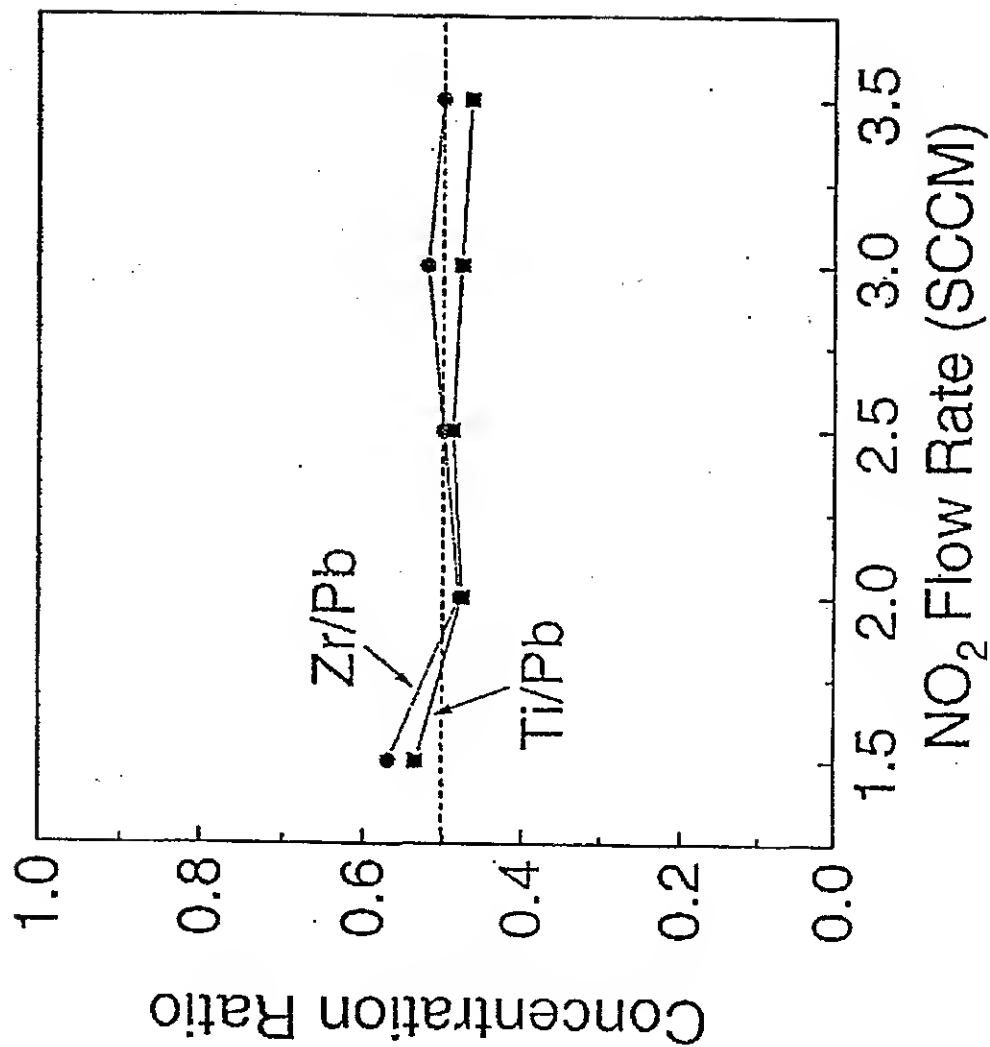
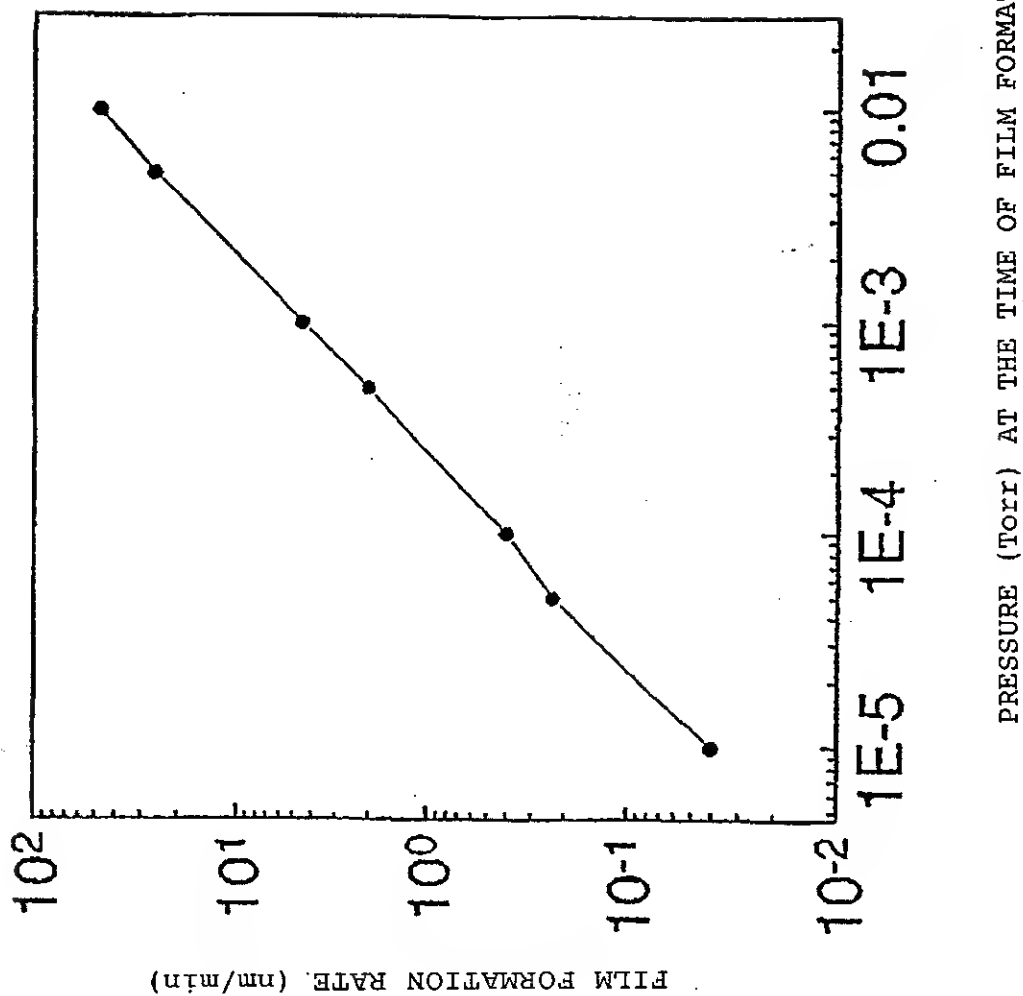
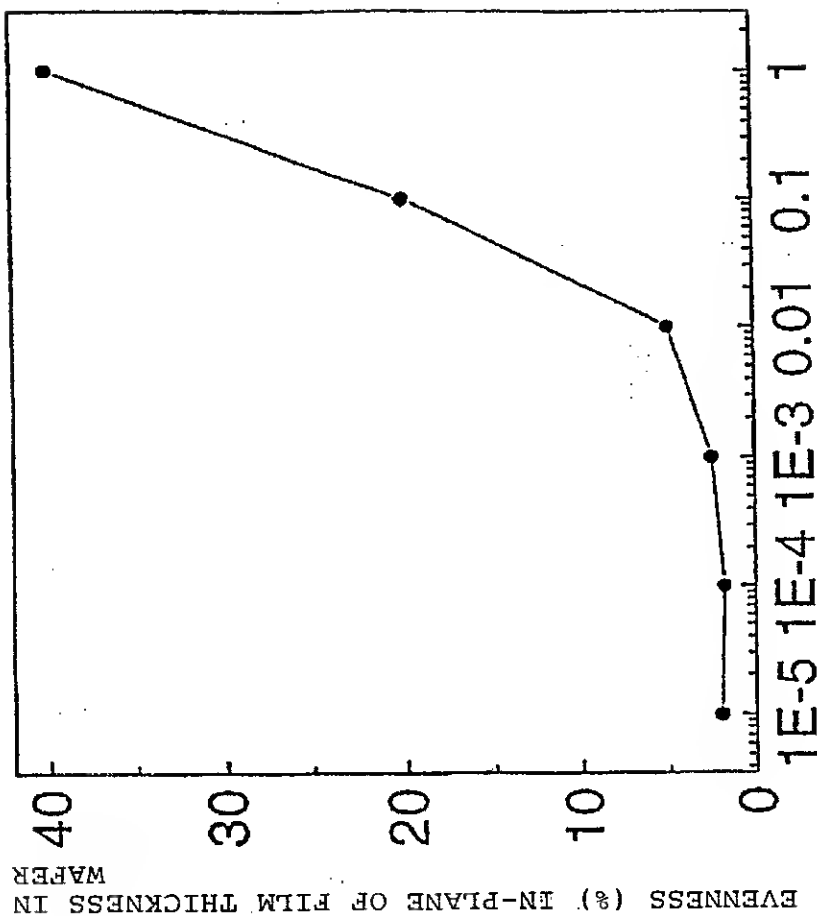


Fig. 15



TOSFO-TOH460

Fig. 16





TOTAL THICKNESS

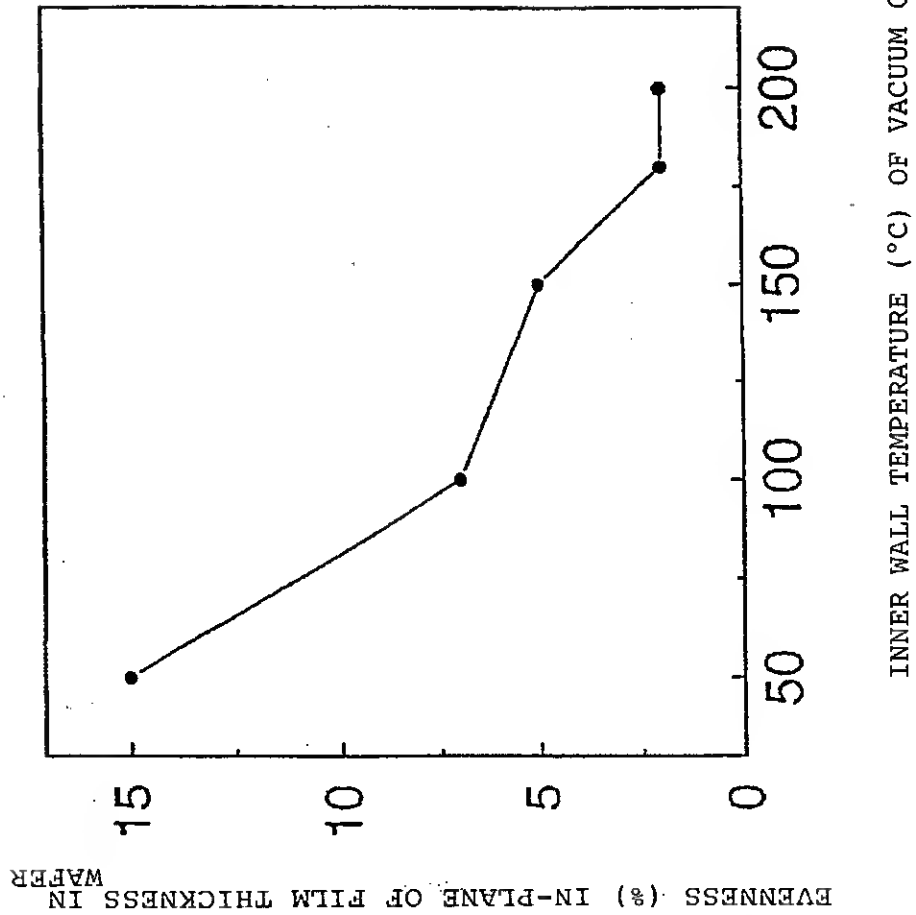


Fig. 17

Fig. 18

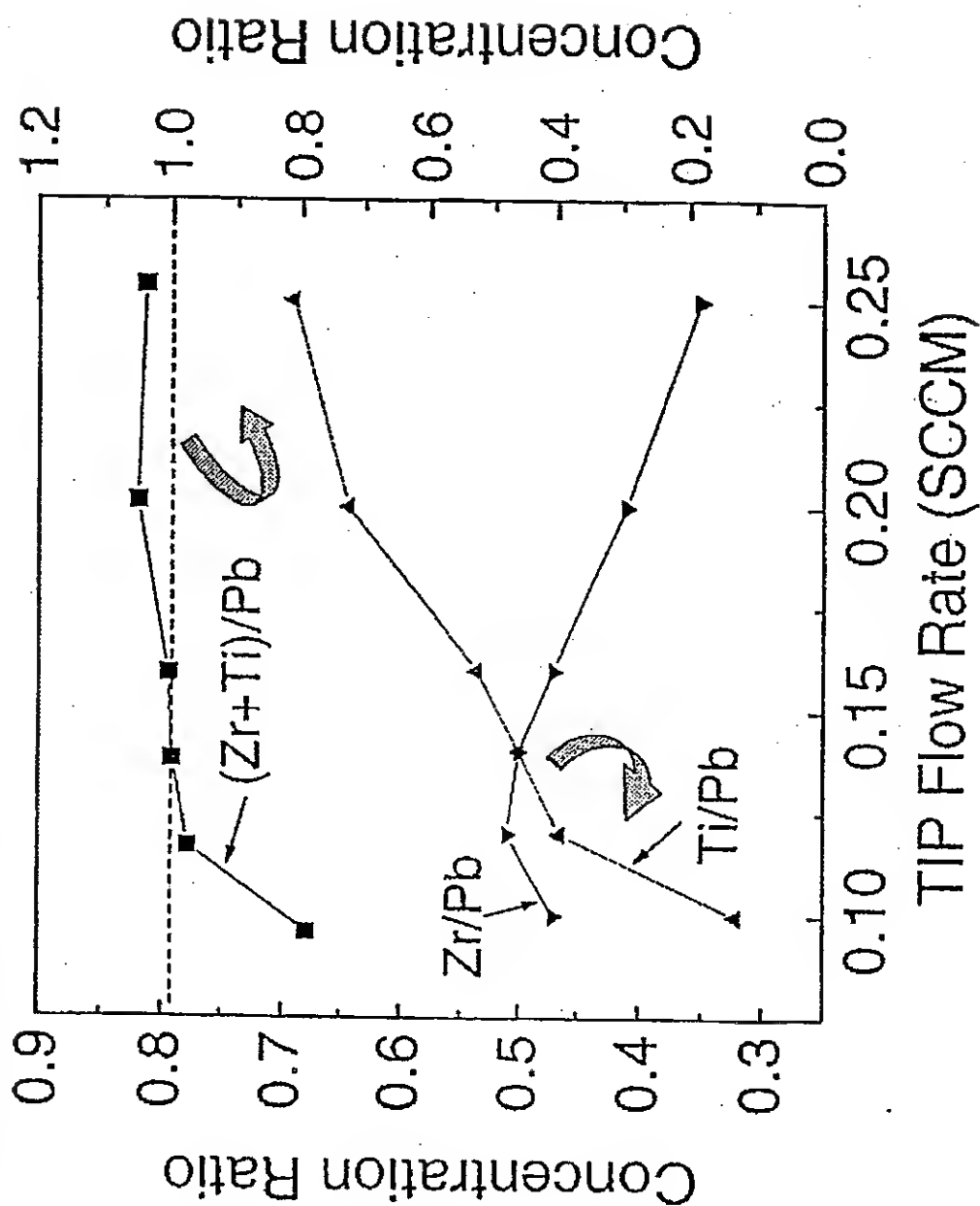


Fig. 19

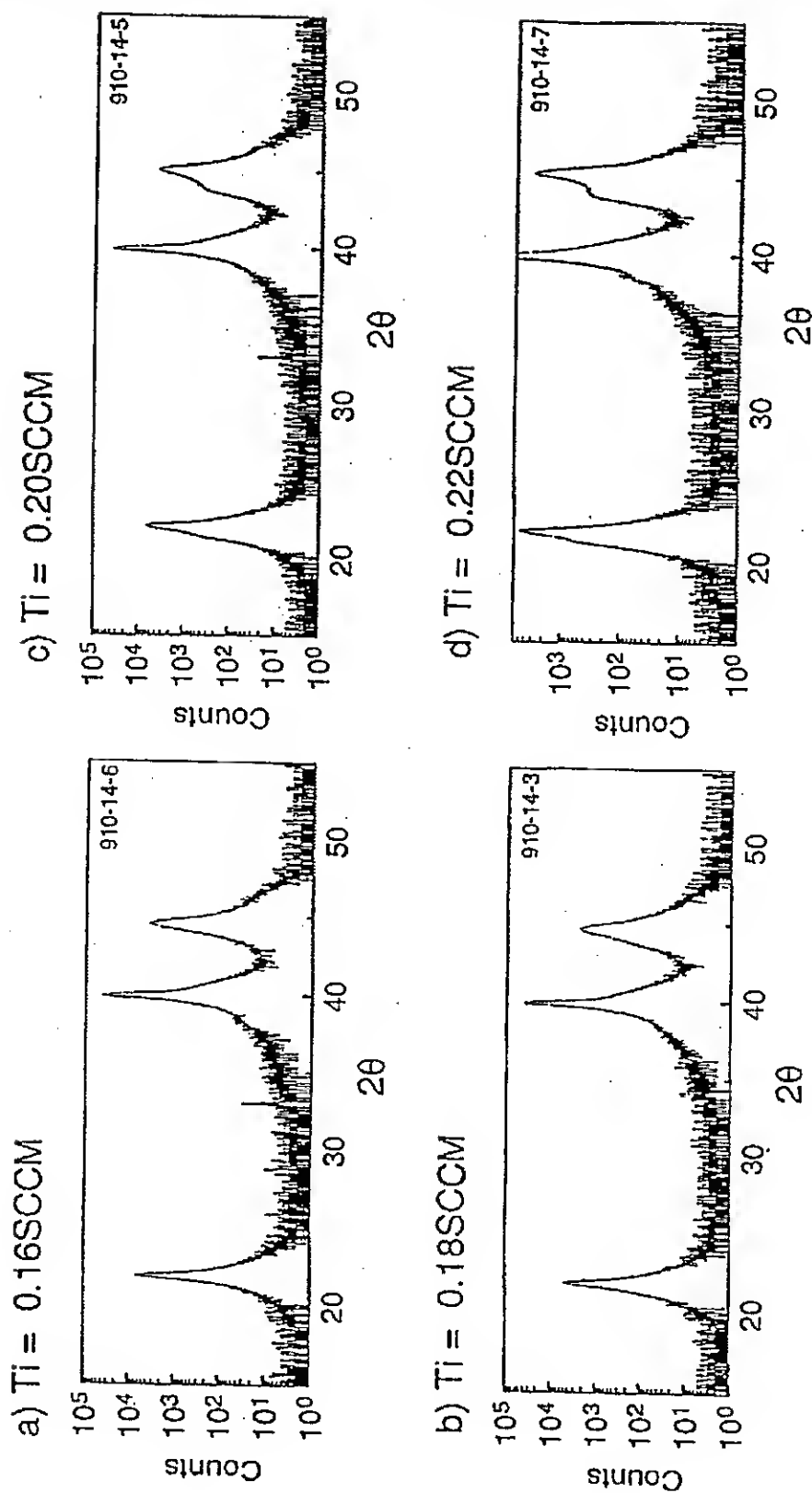


Fig. 20

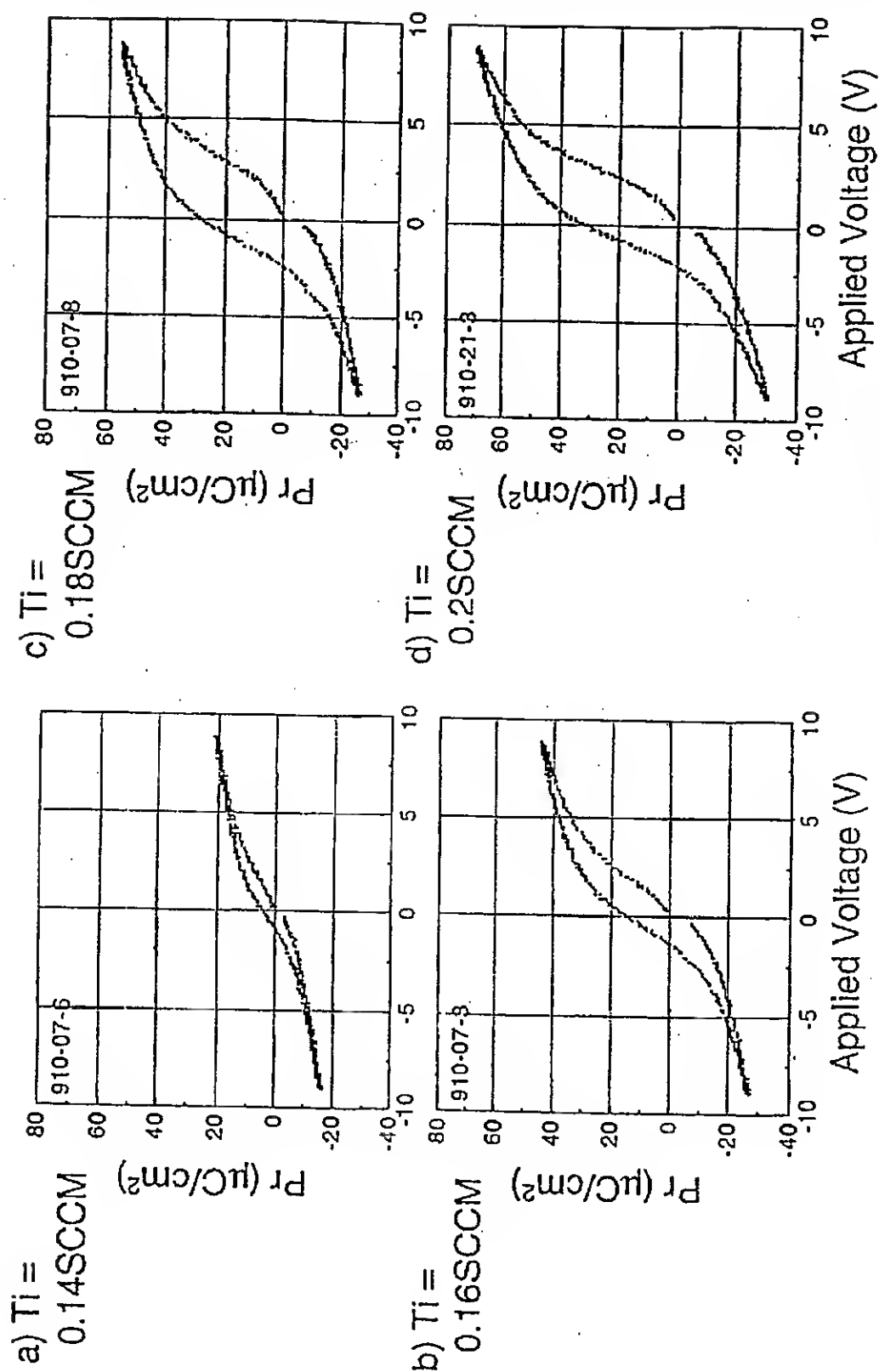


Fig. 21

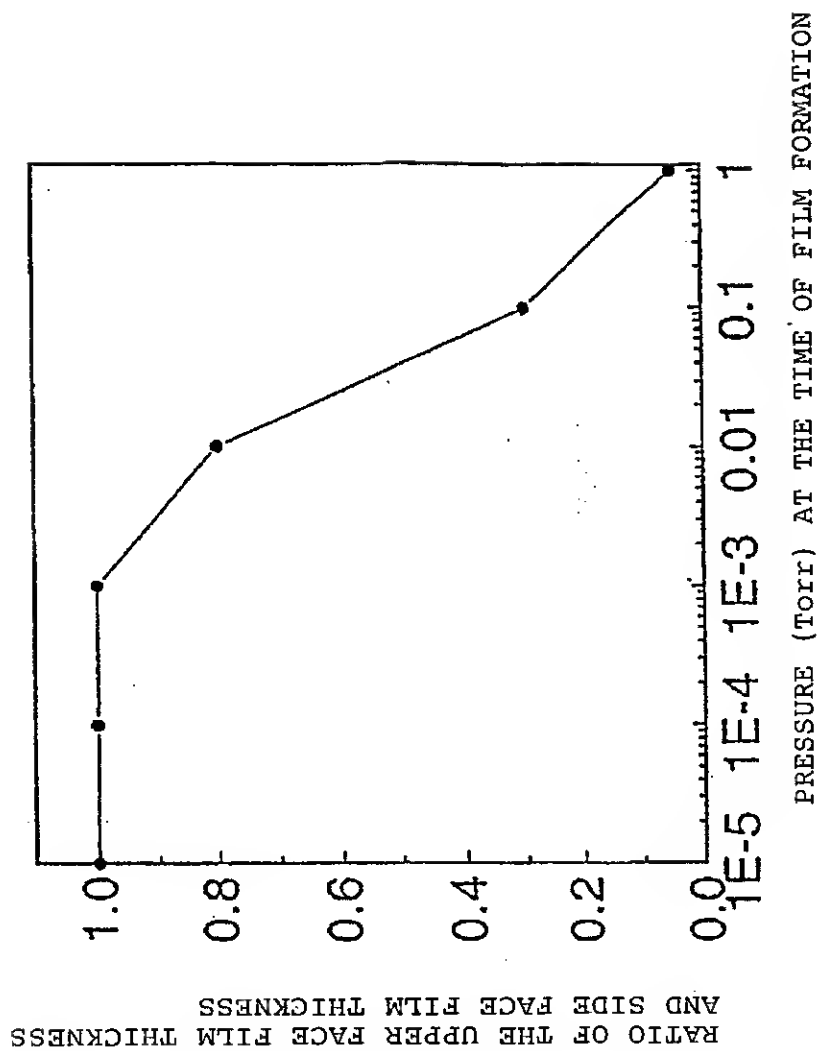
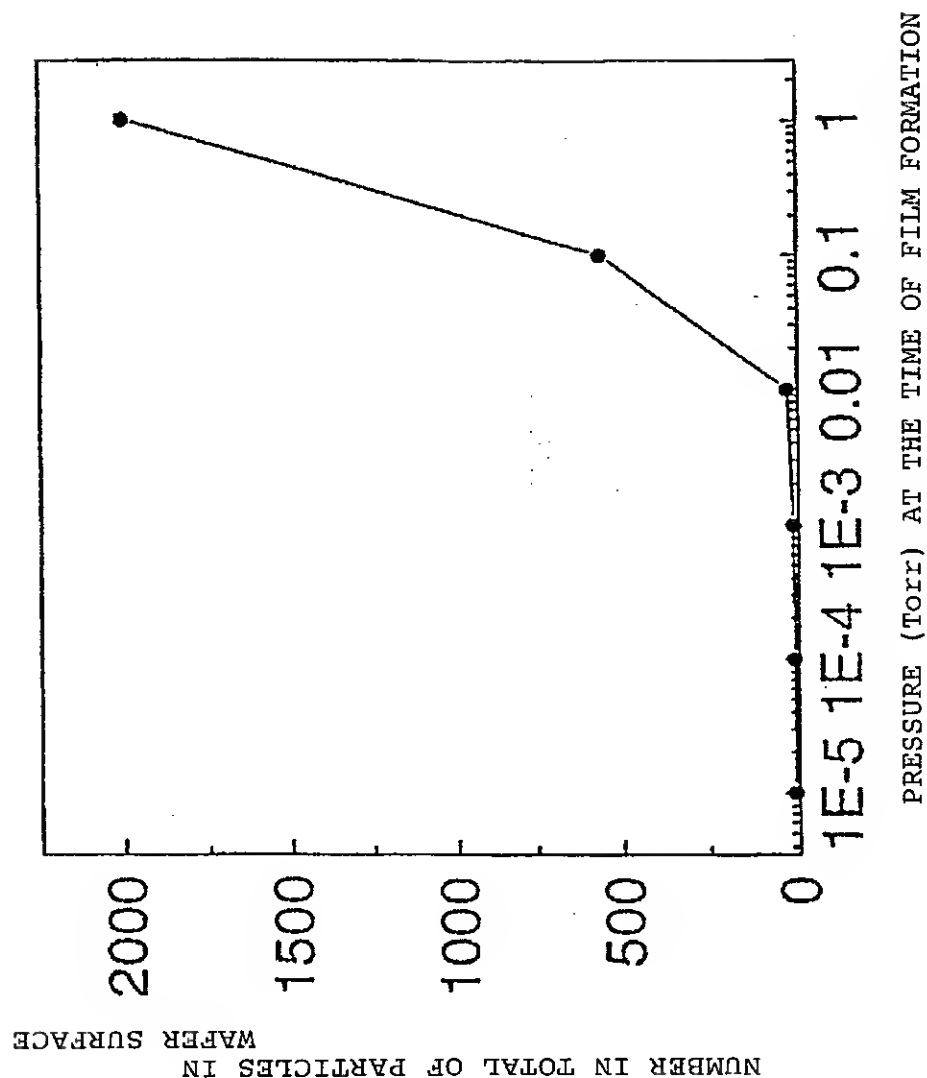


Fig. 22



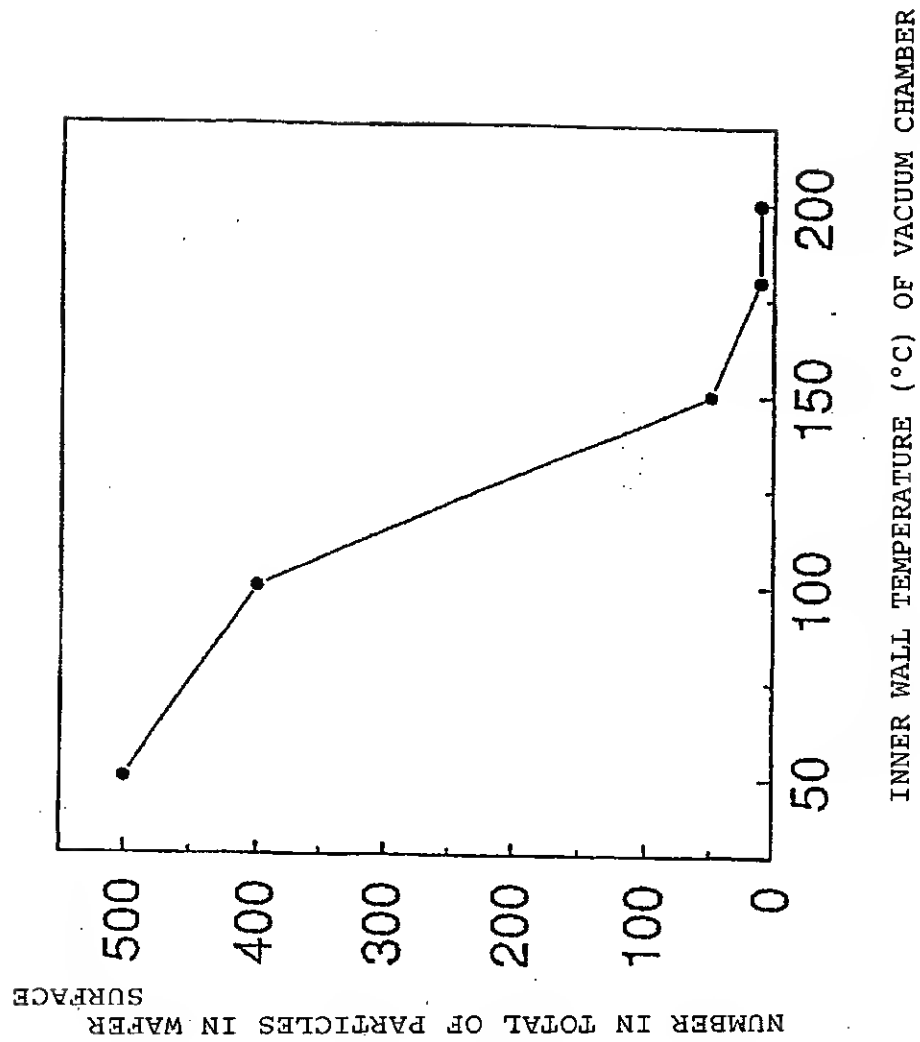


Fig. 23

Fig. 24

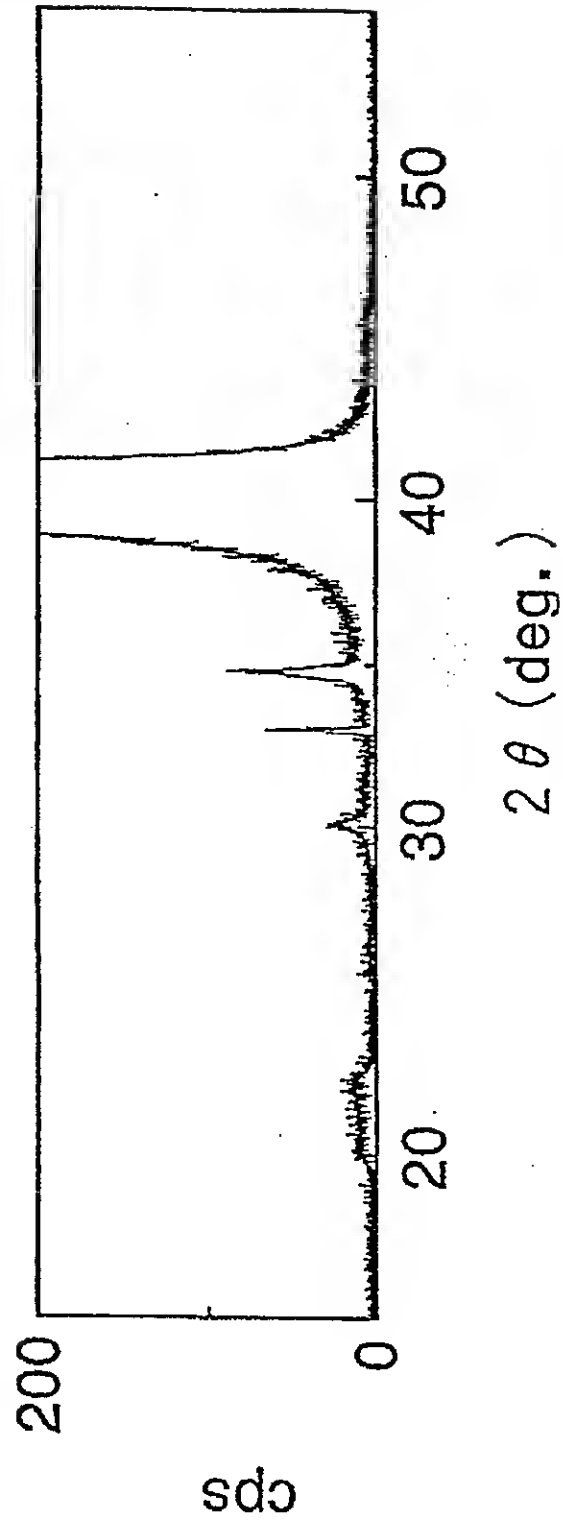
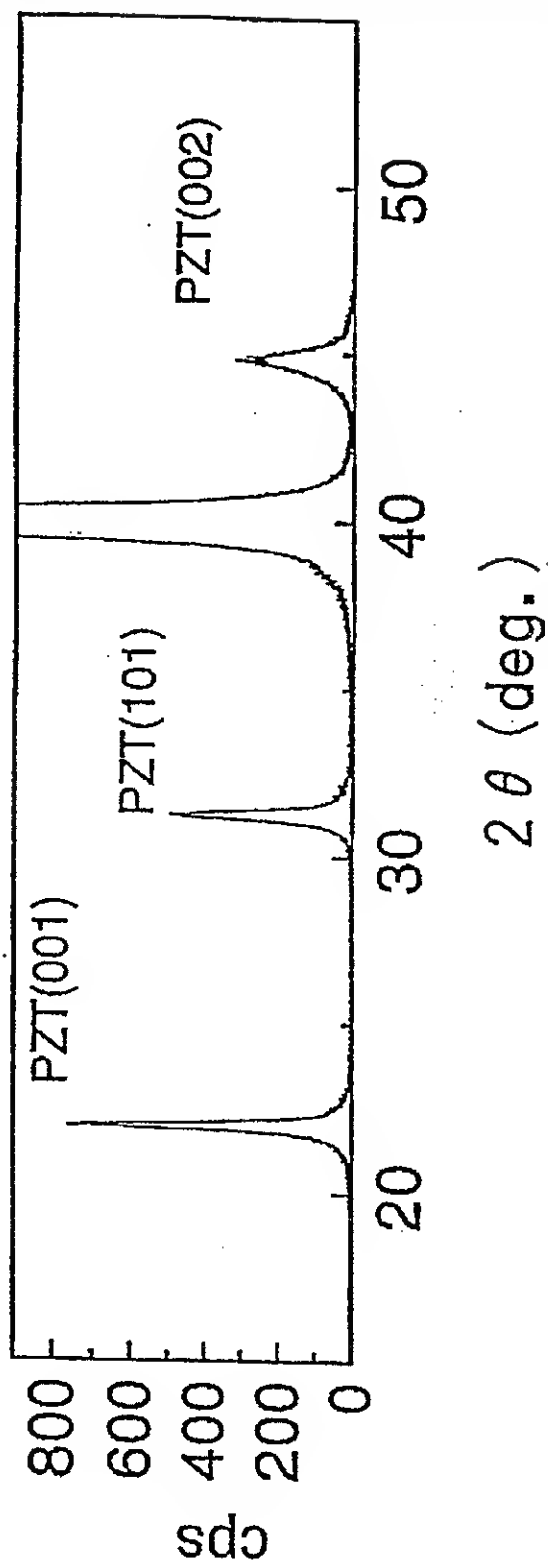




Fig. 25



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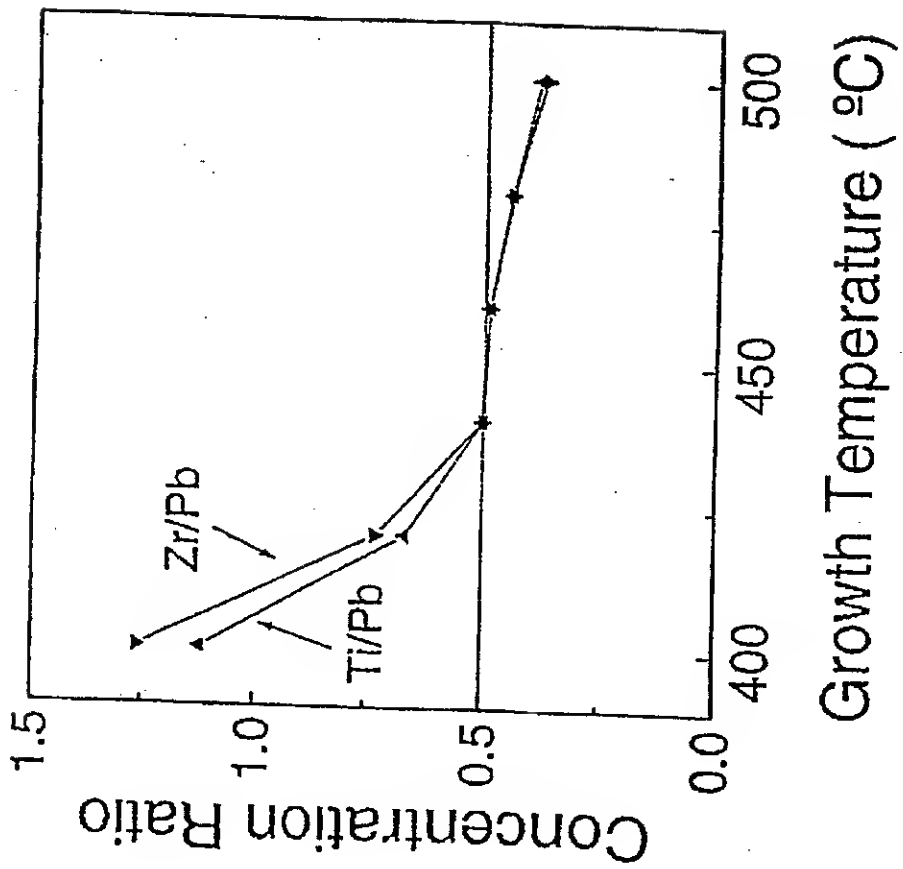


Fig. 27

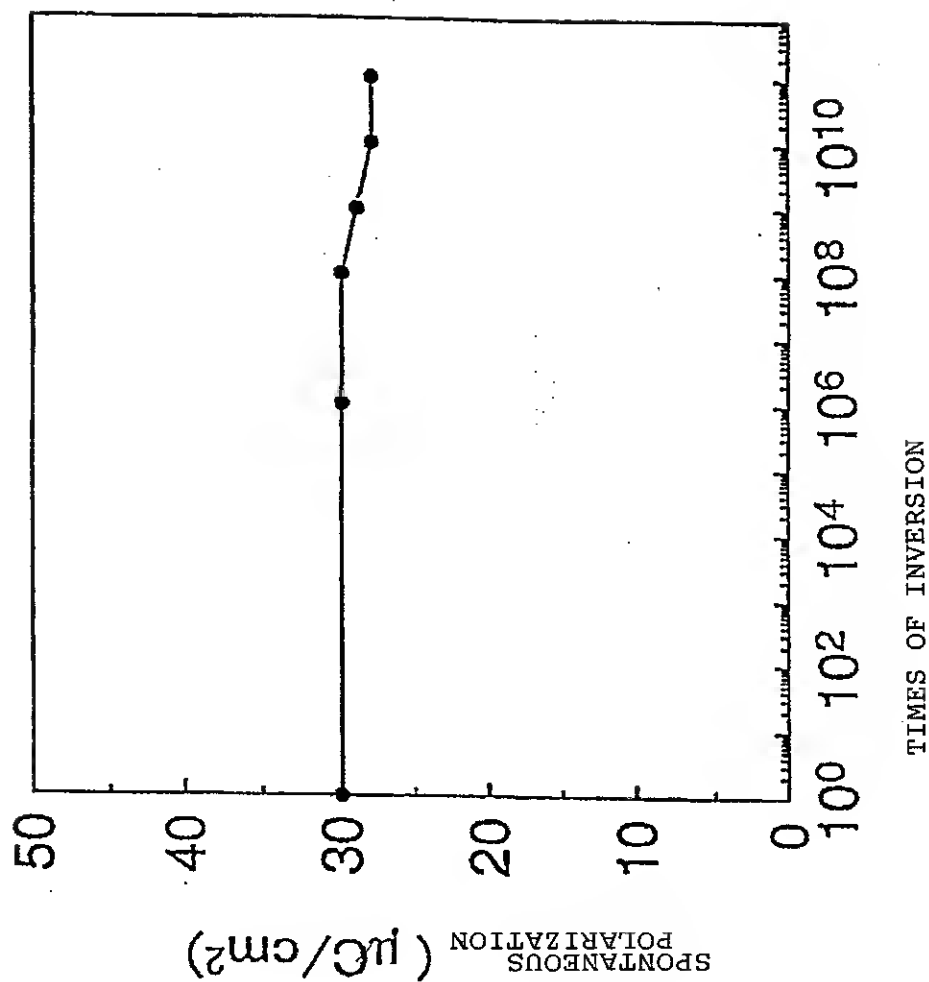


Fig. 28

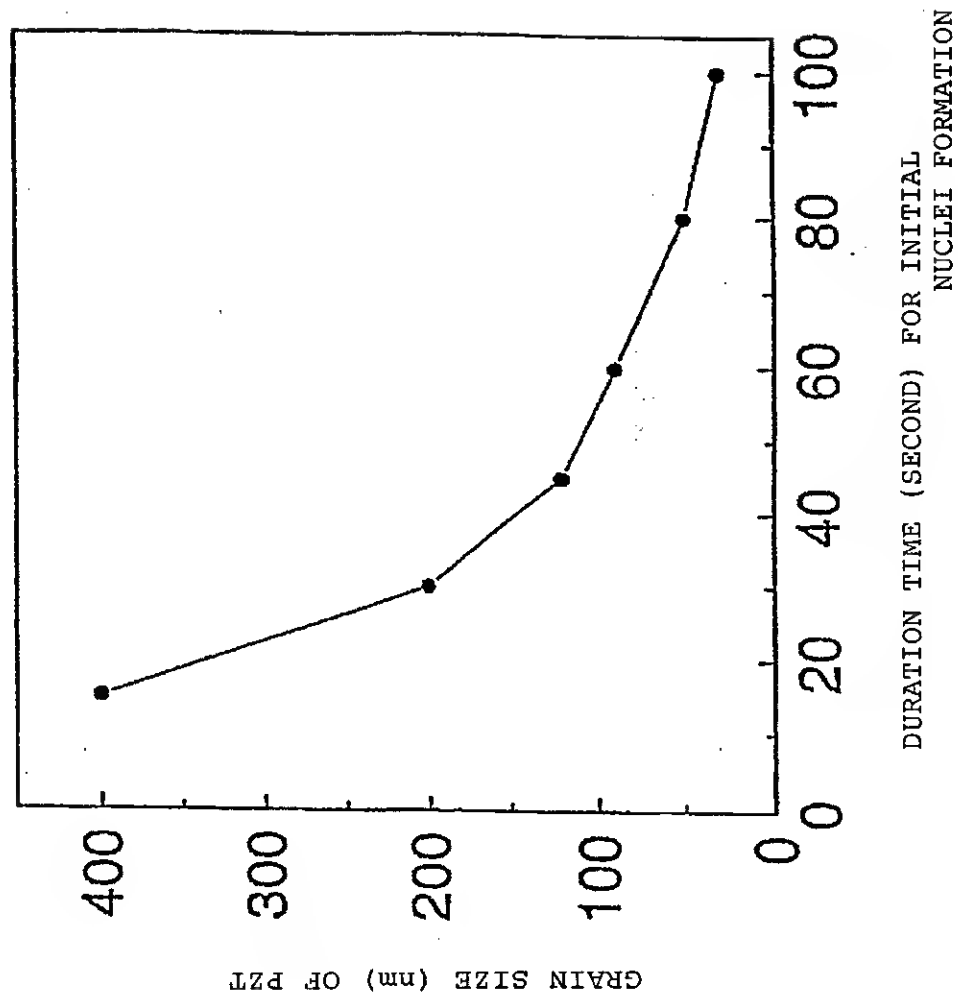


Fig. 29 (A)

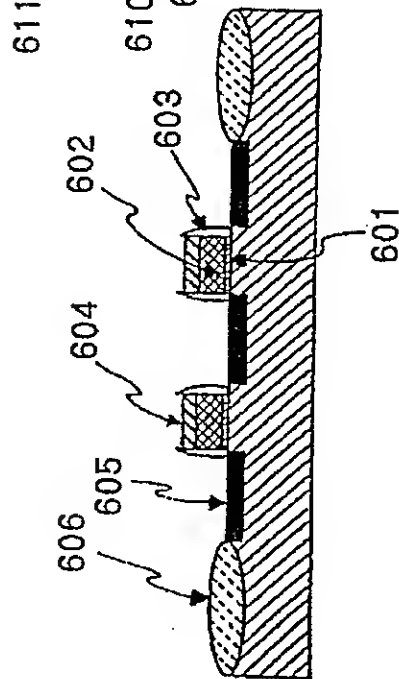


Fig. 29 (B)

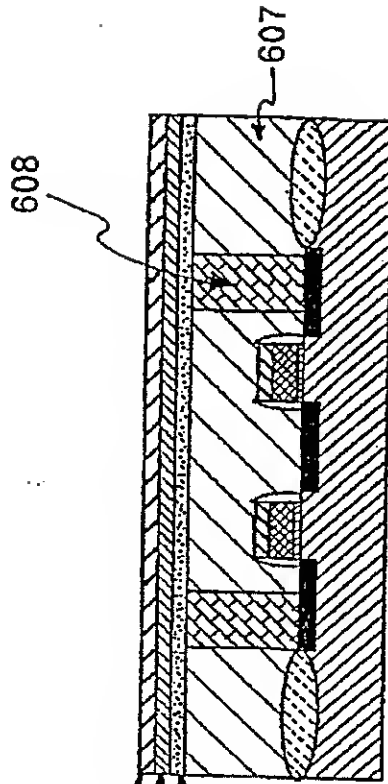


Fig. 29 (C)

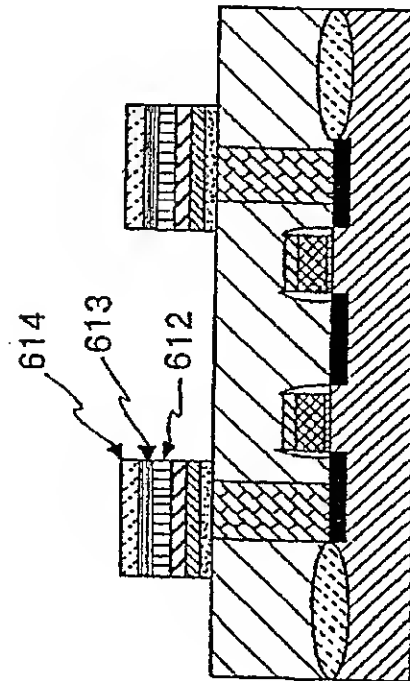


Fig. 29 (D)

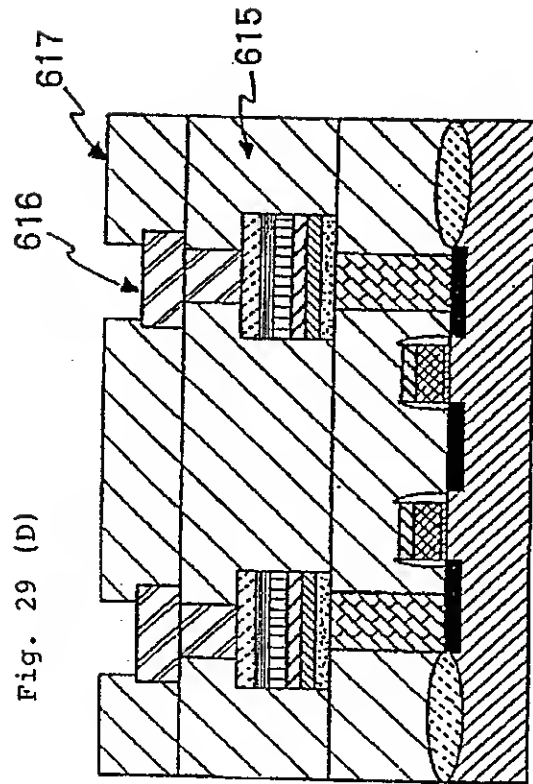


Fig. 30 (A)

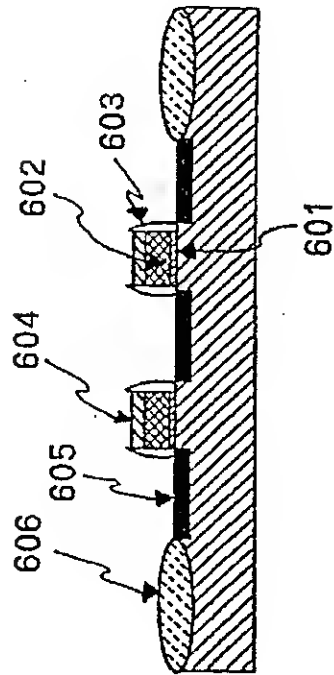


Fig. 30 (B)

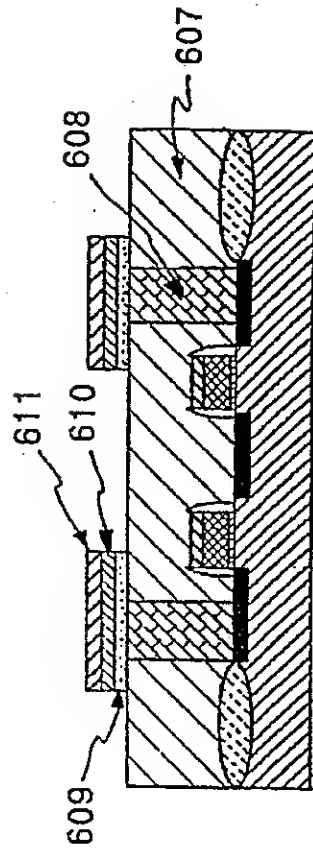


Fig. 30 (C)

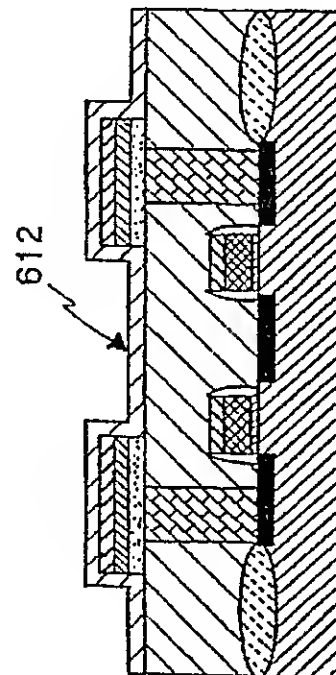


Fig. 30 (D)

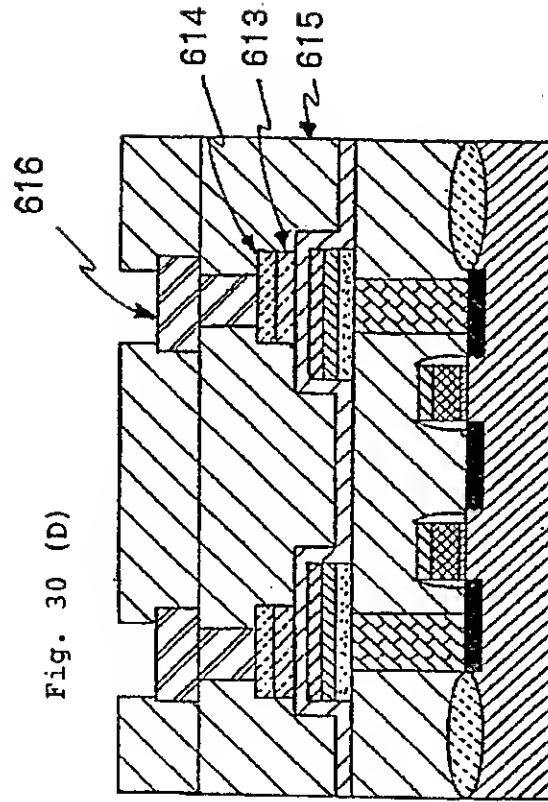


Fig. 31 (A)

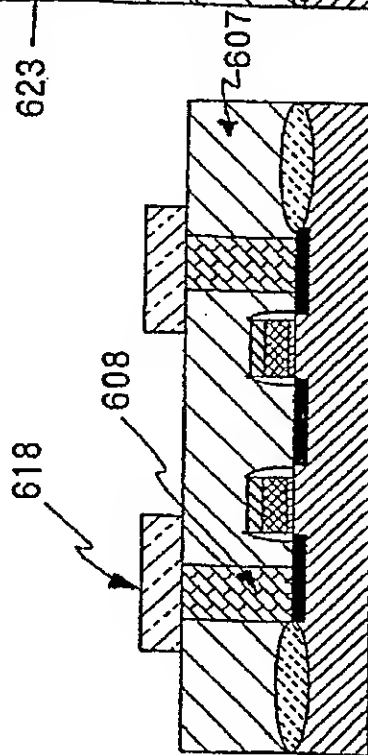


Fig. 31 (B)

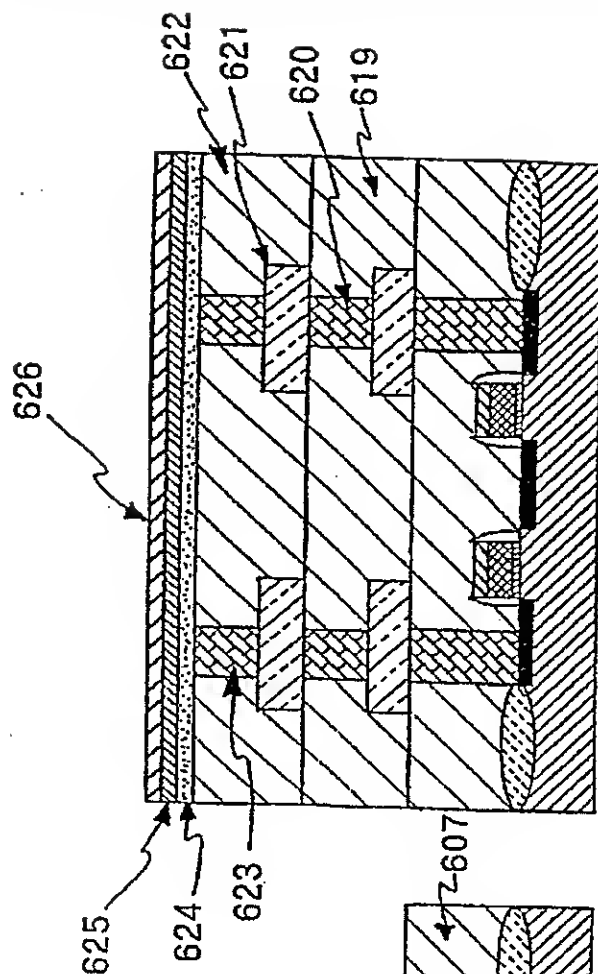


Fig. 32 (C)

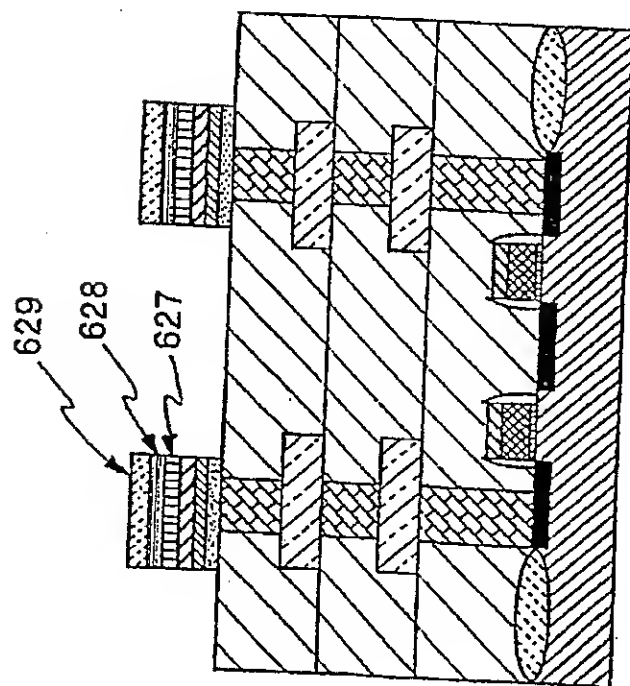


Fig. 32 (D)

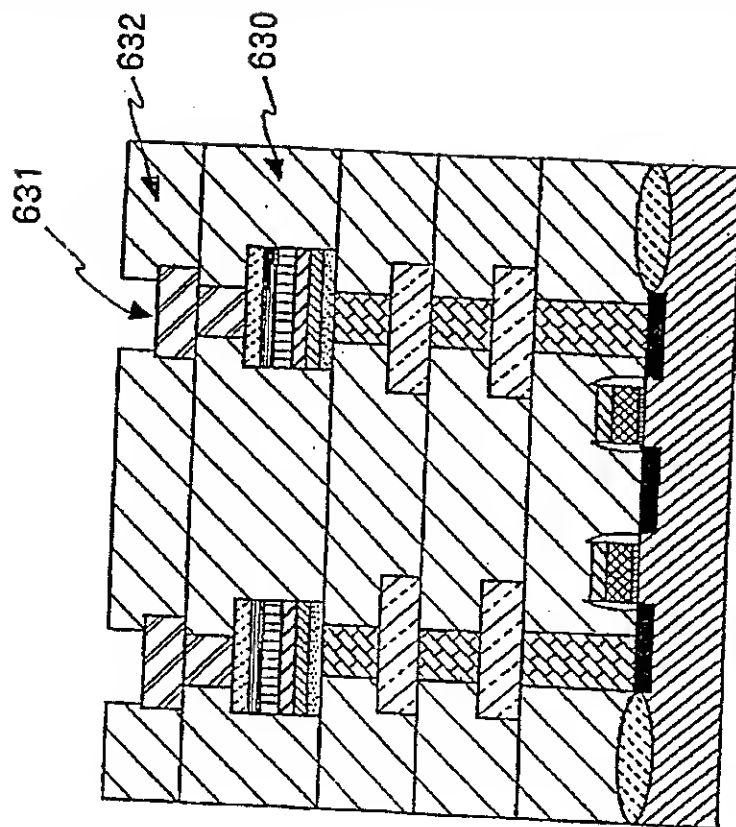






Fig. 34

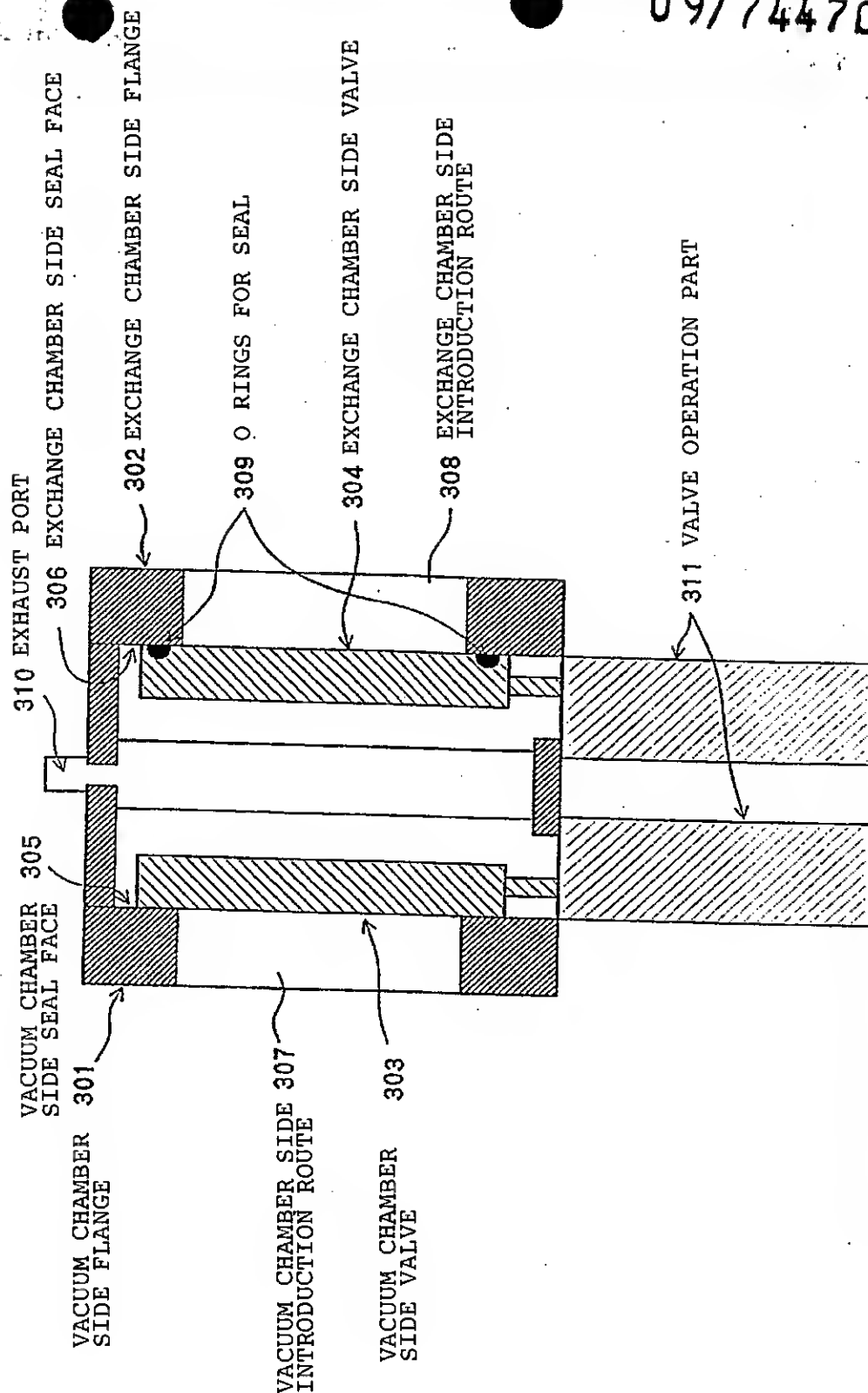


Fig. 35

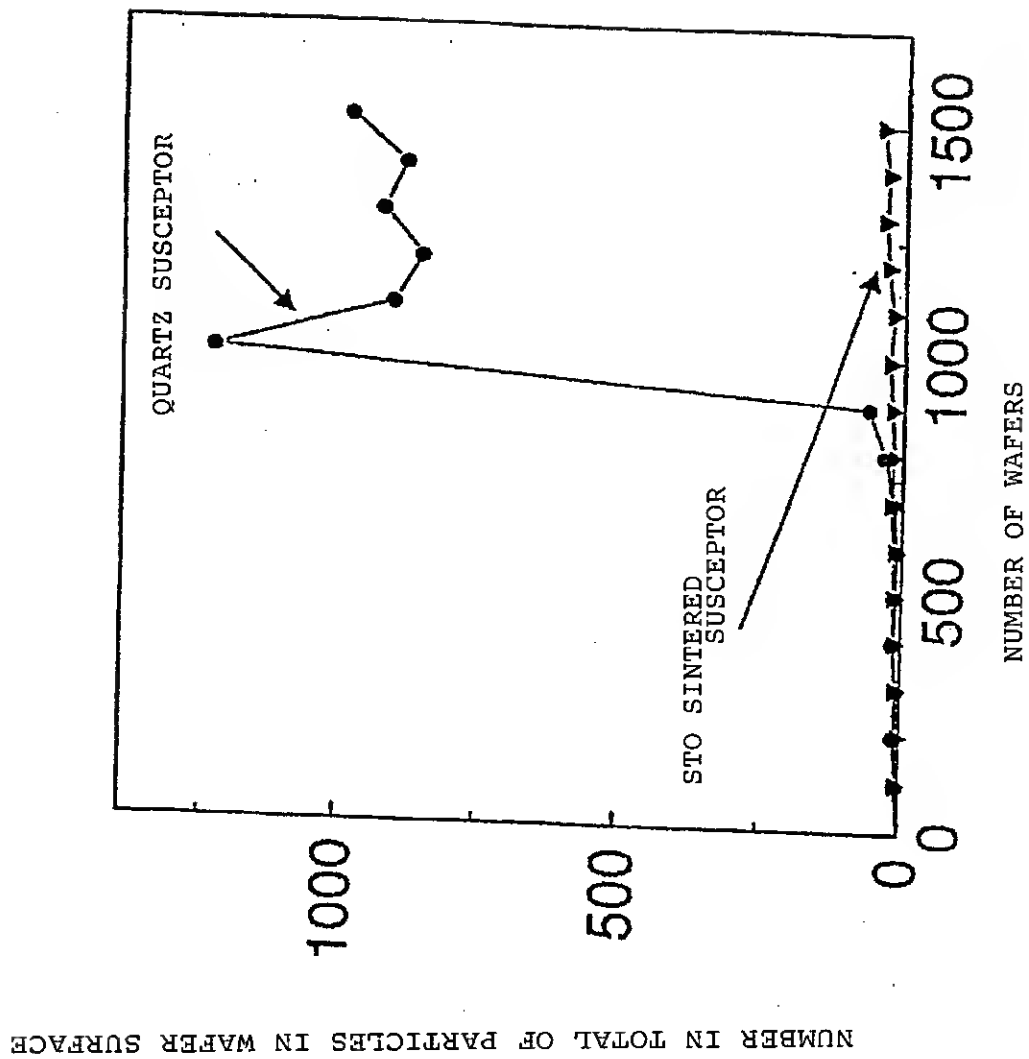


Fig. 36

NUMBER IN TOTAL OF PARTICLES IN WAFER SURFACE

